

SPUTTERING TARGET, METHOD FOR PRODUCING SAME, AND
METHOD FOR PRODUCING SPUTTERING FILM USING
SPUTTERING TARGET

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ABSTRACT

A sputtering target includes crystal grains, has a content of an amorphous phase of 3% by volume or less, and contains at least one metal selected from the group consisting of chromium, molybdenum, and chromium-molybdenum alloys.

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[Figure 4]